

an insulation layer between the gate electrode and the semiconductor layer;
a source electrode and a drain electrode electrically connected with the semiconductor layer;

a color filter layer, contacting the source and drain electrodes only at a portion where said color filter layer is overlapping only edge portions of the source and the drain electrodes;

C1
End
a planarization layer over the color filter layer and the source and the drain electrodes, the planarization layer having an opening exposing the drain electrode thereunder; and

a pixel electrode on the planarization layer and electrically connected with the drain electrode via the opening in the planarization layer.

6. (Twice Amended) A method of forming liquid crystal display (LCD) device,
the method comprising:

C2
forming a substrate;

forming a gate electrode over the substrate;

forming an insulation layer on the gate electrode and the substrate;

forming a semiconductor layer, aligned relative to the gate electrode, on the insulating layer;

forming a source electrode and a drain electrode electrically connected

with the semiconductor layer;

forming a color filter layer, contacting the source and drain electrodes only at a portion where said color filter layer is overlapping only edge portions of the source and the drain electrodes;

forming a planarization layer over the color filter layer and the source and drain electrodes, the planarization layer having an opening exposing the drain electrode thereunder; and

forming a pixel electrode on the planarization layer and electrically connected with the drain electrode via the opening in the planarization layer.

15. (Twice Amended) A liquid crystal display device comprising:

a thin film transistor (TFT) formed on a substrate, including a gate electrode, a source electrode, and a drain electrode;

a color filter layer, contacting the source and drain electrodes only at a portion where said color filter layer is overlapping only edge portions of the source and drain electrodes;

a planarization layer formed on the TFT and on the color filter; and

a pixel electrode formed on the planarization layer and electrically contacting the drain electrode.

21. (Twice Amended) A method of manufacturing a liquid crystal display device, the method comprising:

providing a substrate;

forming a gate electrode on the substrate;

depositing sequentially a gate insulating layer, a pure semiconductor layer and a doped semiconductor layer over the substrate;

etching the pure semiconductor layer and the doped semiconductor layer to form an active layer;

forming a source electrode and a drain electrode on the active layer;

forming a color filter, the color filter, contacting the source and drain electrodes only at a portion where said color filter layer is overlapping only an edge portion of the source and drain electrodes;

etching a portion of the doped semiconductor layer between the source and drain electrodes to form a channel region of a resulting intermediate structure;

forming a planarization layer over the intermediate structure, the planarization layer including a drain contact hole to expose a portion of the drain electrode; and

forming a pixel electrode on the planarization layer, the pixel electrode electrically contacting the drain electrode via the drain contact hole.

22. (Twice Amended) A method of manufacturing a liquid crystal display device, the method comprising:

providing a substrate, the substrate including first and second regions;

forming a thin film transistor (TFT) on the first region of the substrate, the

*Def
End* TFT having a gate electrode, an active layer, and source and drain electrodes;

forming a color filter on a second region of the substrate, the color filter, contacting the source and drain electrodes only at a portion where said color filter layer is overlapping only edge portions of the source and drain electrodes;

forming a planarization layer on the TFT and the color filter, the planarization layer including a drain contact hole to expose a portion of the drain electrode; and

forming a pixel electrode on the planarization layer, the pixel electrode electrically contacting the drain electrode via the drain contact hole.
